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(54) Title: HYBRID CMP CONDITIONING HEAD

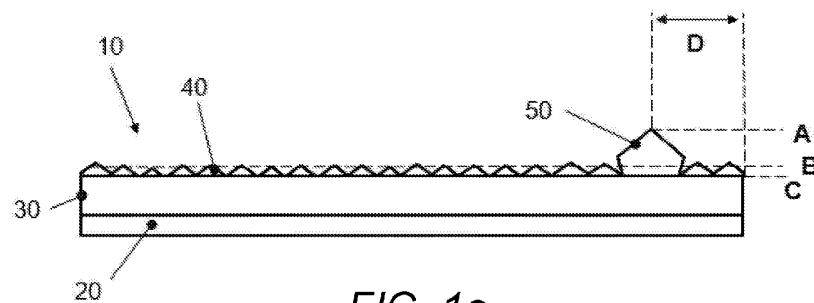


FIG. 1a

(57) Abstract: The present invention relates to a conditioning head which includes a substrate comprising a substrate surface; and at least one raised non-planar abrasive region relative to the substrate surface. The non-planar abrasive region comprises an edge shaving region and a point cutting region, the ratio of the surface area of the edge shaving region to the point cutting region is at least 2:1; and wherein the cutting point region comprises one or more protrusions extending no more than 250 microns from the mean height of the edge shaving region



WO 2020/044011 A1